

### The Diffusion Coefficient

$$D = D_o \exp\left(-\frac{E_A}{kT}\right) \quad (\text{as usual, an Arrhenius relationship})$$

**Table 4.1** Typical Diffusion Coefficient Values for a Number of Impurities.

Element	$D_o(\text{cm}^2/\text{sec})$	$E_A(\text{eV})$
B	10.5	3.69
Al	8.00	3.47
Ga	3.60	3.51
In	16.5	3.90
P	10.5	3.69
As	0.32	3.56
Sb	5.60	3.95

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### Diffusion Coefficient Graphs

**Substitutional & Interstitial Diffusers**

Fig. 7.1

**Interstitial Diffusers**  
↳ Note the much higher diffusion coeffs. than for substitutional

Fig. 7.2

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### Metallurgical Junction Depth, $x_j$

$x_j$  = point at which diffused impurity profile intersects the background concentration,  $N_B$

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### Expressions for $x_j$

- Assuming a Gaussian dopant profile: (the most common case)

$$N(x_j, t) = N_o \exp\left[-\left(\frac{x_j}{2\sqrt{Dt}}\right)^2\right] = N_B \rightarrow x_j = 2\sqrt{Dt \ln\left(\frac{N_o}{N_B}\right)}$$

- For a complementary error function profile:

$$N(x_j, t) = N_o \operatorname{erfc}\left(\frac{x_j}{2\sqrt{Dt}}\right) = N_B \rightarrow x_j = 2\sqrt{Dt} \operatorname{erfc}^{-1}\left(\frac{N_B}{N_o}\right)$$

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### Sheet Resistance

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- Sheet resistance provides a simple way to determine the resistance of a given conductive trace by merely counting the number of effective squares
- Definition:**

$$R = \frac{\rho L}{A} = \left(\frac{\rho}{t}\right) \frac{L}{W} = R_s \left(\frac{L}{W}\right)$$

ohms per square  
Ω/D

sheet resistance      # unit squares of material in the resistor

eg.:

uniformly doped material w/ resistivity  $\rho = \frac{1}{\sigma}$

$\sigma = \text{conductivity} = q(\mu_n n + \mu_p p)$

eg.:

∴  $R = R_s \times 5$
- What if the trace is non-uniform? (e.g., a corner, contains a contact, etc.)

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### # Squares From Non-Uniform Traces

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### Sheet Resistance of a Diffused Junction

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- For diffused layers:
 

Sheet resistance

$$R_s = \frac{\rho}{x_j}$$

Effective resistivity

$$= \left[ \int_0^{x_j} \sigma(x) dx \right]^{-1}$$

Majority carrier mobility

$$= \left[ \int_0^{x_j} q \mu N(x) dx \right]^{-1}$$

Net impurity concentration

[extrinsic material]
- This expression neglects depletion of carriers near the junction,  $x_j \rightarrow$  thus, this gives a slightly lower value of resistance than actual
- Above expression was evaluated by Irvin and is plotted in "Irvin's curves" on next few slides
  - Illuminates the dependence of  $R_s$  on  $x_j$ ,  $N_0$  (the surface concentration), and  $N_B$  (the substrate background conc.)

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### Irvin's Curves (for n-type diffusion)

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**Example.** p-type

**Given:**

- $N_B = 3 \times 10^{16} \text{ cm}^{-3}$
- $N_0 = 1.1 \times 10^{18} \text{ cm}^{-3}$
- (n-type Gaussian)
- $x_j = 2.77 \mu\text{m}$

Can determine these given known prep. and drive conditions

Determine the  $R_s$ .

Using Fig. 7.7:

$R_s x_j = 470 \Omega \cdot \mu\text{m}$

∴  $R_s = \frac{470}{2.77} = 170 \Omega/\square$

*No.  $N_B, x_j, R_s \rightarrow$  given any 3, can find the 4th!*

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